

Fabrication of CIGS films by using MBE for tandem solar cells

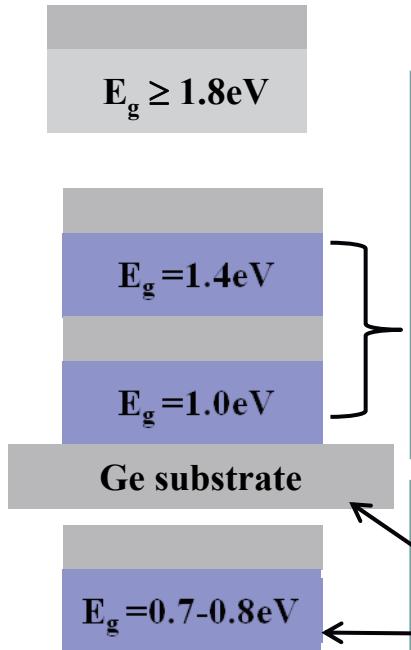
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Objective:

development of high-efficiency compound semiconductor-based tandem solar cells

Efficiency goal at 2010:

development of technologies to demonstrate over 20%-efficiency tandem solar cells



CIGS-based tandem structures

Mechanical –stack

- improvement of conversion efficiencies of solar cells on TCO back contact
- bonding techniques

Monolithic

- low-temperature absorber deposition
- temperature-resistive buffer layer

Narrow-gap material

- epitaxial solar cells on Ge substrate
- novel narrow-gap material

Experimental

Growth method: conventional Molecular beam epitaxy

Sources: Cu(7N), In (7N), Se(6N)

Substrate: Ge (001)

Growth temperature: 450°C

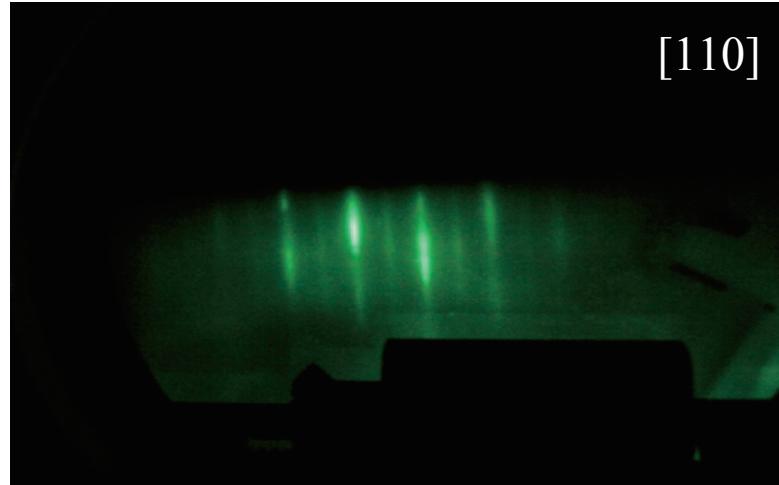
Cu/In ratios: $\gamma=0.4\text{-}2.2$ (changing the In beam flux)

Substrate etching solution: 1HF:1H₂O₂:30H₂O

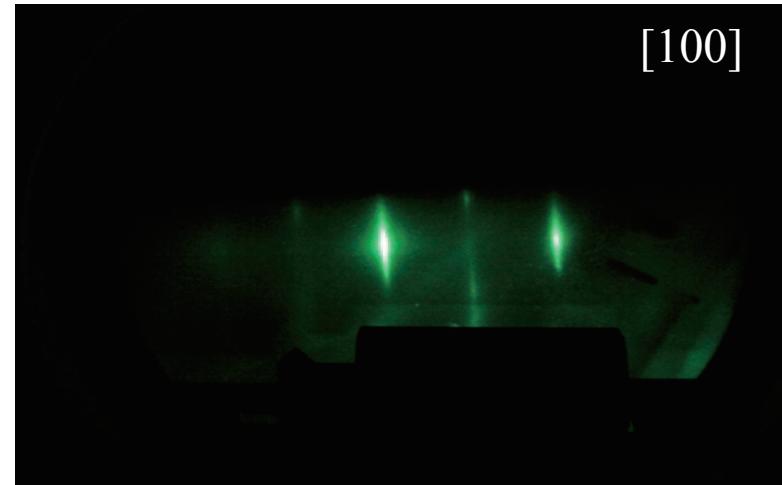
Thermal cleaning process : 640°C

Characterization: XRD, RHEED, SEM,EPMA

<RHEED patterns from thermal clean Ge(001) surface>



[110]

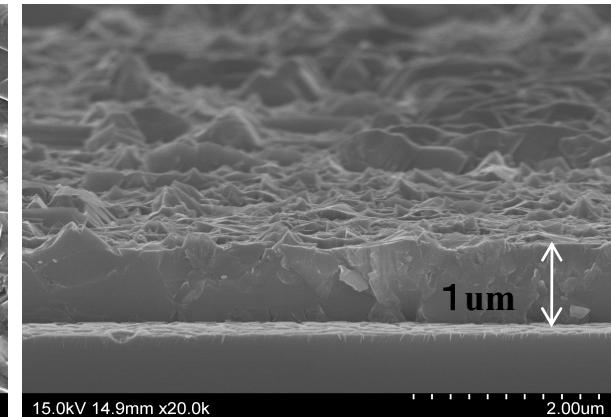
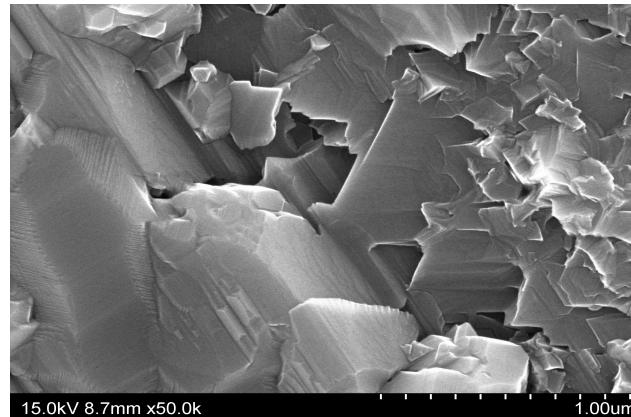
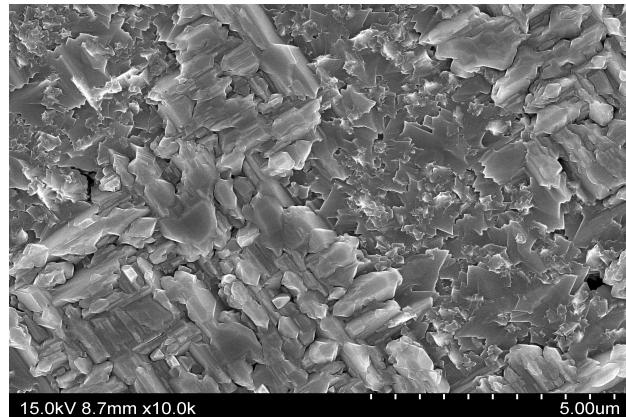
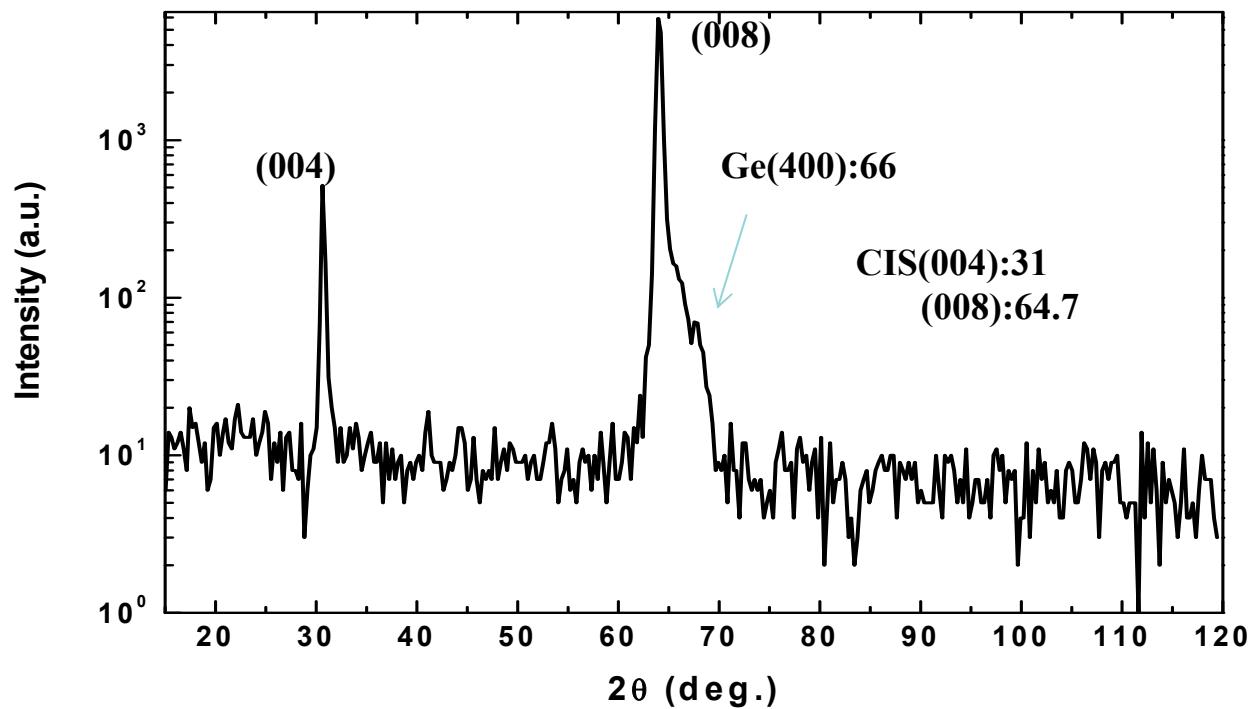


[100]

Results

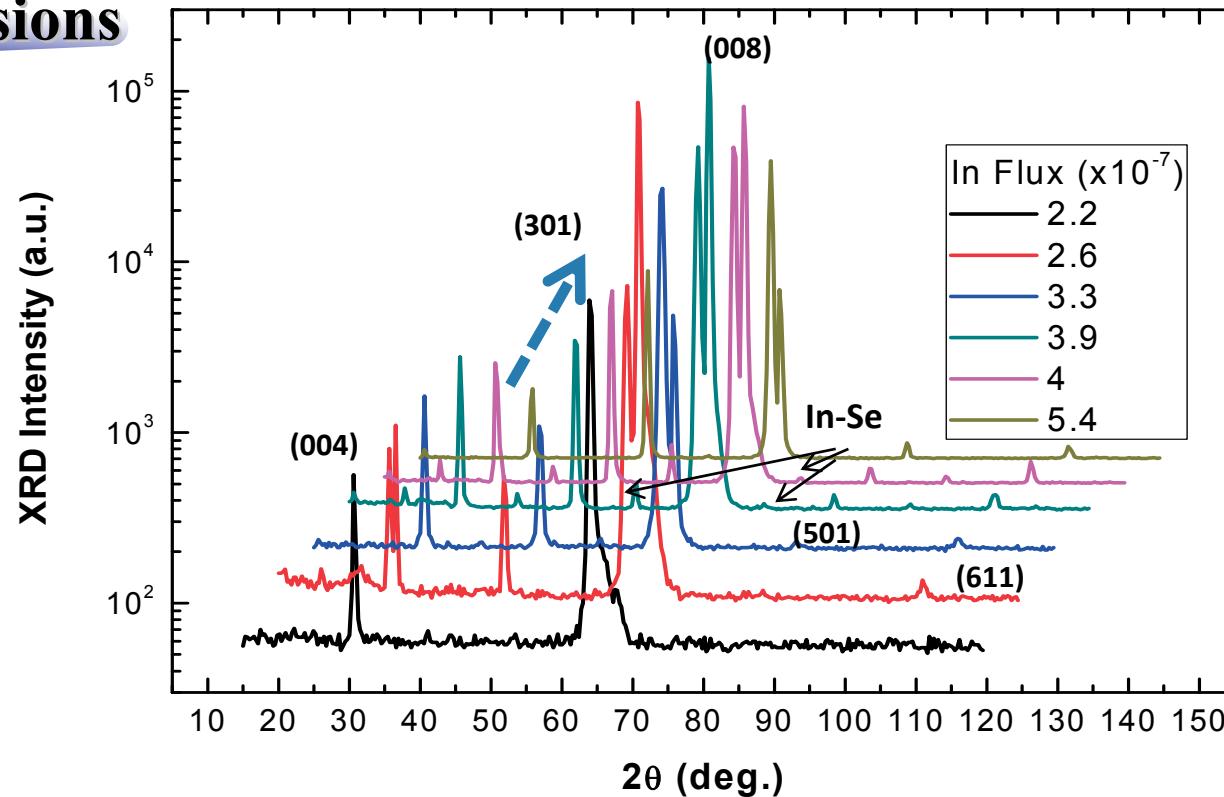
In:745 °C 2.2×10^{-7}
Cu:1005 °C 1.1×10^{-7}
 T_{sub} : 450 °C

EPMA (Cu/In)
5kV :0.85
7kV :1.07
15kV :1.19



Near stoichiometric CIS film was not observed second phase

Conclusions



CuInSe₂ (CIS) films with Cu/In ratios of $\gamma=0.4\text{--}2.2$ have been grown on (001)-oriented Ge substrates by molecular beam epitaxy at substrate temperature of $T_s=450^\circ\text{C}$.

***In situ* RHEED analysis indicated the epitaxial growth as well as the chalcopyrite structure.**

RHEED patterns along the [-100] direction showed the spots characteristic of the chalcopyrite structures, also indicating the c-axis normal to the substrate.

No secondary phase detected in XRD at Cu-rich and near stoichiometric but In-rich CIS films were observed.